Documentation for Participants in the MPC580 Multiproject Chip-Set

A Collection of Information and Instructions conveyed to the Participating Designers, along with their Packaged Chips.

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7 July 1980

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A special acknowledgement from Ted Strollo

MPC580 is a follow on to the very successful MPC79 effort. It would not have been possible without the incredible behind the scenes help from the SSL - LSI people - especially Lynn Conway, Alan Bell, Richard Lyon, and Martin Newell. I also want to extend my thanks to the members of my group (VCI) who helped pull this off - Kevin Gillette, Glenn Krasner, Maureen Stone, and Wayne Wilner. While I signed off on all the formal MPC580 communications, it was this team effort that made MPC580 happen. To every member of this team I extend my personal gratitude and love.

Forward

A total of 171 VLSI system design projects, created by 15 universities/organizations, are included in the MPC580 chip-set. This is an amazing growth from the 82 projects in MPC79, and we expect this appetite for custom VLSI system design projects to continue to grow!

This document provides basic information that the participating project coordinators and designers may use (i) to determine which packaged project belongs to which designer(s), (ii) to determine their project pinouts and prepare their chips for testing, (iii) to estimate the maximum clock rates for their projects, (iii) to study the details of the starting frame, and (iv) to learn more about the projects of the other participants.

List of Sections:

1. Introduction and Overview
2. Some Basic Instructions for the Designers
3. List of Designers and Their Projects
4. Starting Frame Documentation
5. Electrical & Process Measurements
6. Request for Feedback and Further Plans